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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Ko et al.

Serial No.: 09/711,324

Filed: November 13, 2000

For: ETCHANT WITH SELECTIVITY
FOR DOPED SILICON DIOXIDE OVER
UNDOPED SILICON DIOXIDE AND
SILICON NITRIDE, PROCESSES WHICH
EMPLOY THE ETCHANT, AND
STRUCTURES FORMED THEREBY

Confirmation No.: 7008

Examiner: K. Chen

Group Art Unit: 1765

Attorney Docket No.: 2269-3526.4US
(97-1136.05/US)

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AMENDMENT ACCOMPANYING REQUEST FOR CONTINUED EXAMINATION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This Amendment follows the April 21, 2003, Decision by the Board of Patent Appeals and Interferences affirming the rejections that were previously presented in the above-referenced application, and accompanies a Request for Continued Examination.

Amendments to the Claims begin on page 2 of this paper; and

Remarks start at page 8 of this paper.

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